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2811

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Justin K. Brask et al.

Serial No.: 10/626,336

Filed: July 24, 2003

For: Forming a High Dielectric Constant
Film Using Metallic Precursor

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Art Unit: 2811

Examiner: Ori Nadav

Atty Docket: ITL.1022US
P16709

Assignee: Intel Corporation

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed February 23, 2005, reconsideration is requested in view of the following remarks.

Date of Deposit: March 15, 2005

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L. Hayden
Cynthia L. Hayden